

APPENDIX A
"CLEAN" VERSION OF EACH PARAGRAPH/SECTION/CLAIM
37 C.F.R. § 1.121(b)(ii) AND (c)(i)

CLAIMS (with indication of amended or new):

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1. (AMENDED) A substrate method for cleaning a substrate by supplying a cleaning solution thereto, comprising the steps of:
supplying said cleaning solution having ozone dissolved therein to said substrate; and
subsequently irradiating said cleaning solution supplied to said substrate with ultraviolet light.

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9. (AMENDED) A substrate treating apparatus comprising:
a support that supports a substrate;
a cleaning solution supply that supplies a cleaning solution having ozone dissolved therein to said substrate;
an ultraviolet emitter that emits ultraviolet light to said substrate; and
a control which controls the ultraviolet emitter so that, during a cleaning process in which said cleaning solution is supplied from said cleaning solution supply to said substrate supported by said support, said ultraviolet emitter emits ultraviolet light to said cleaning solution supplied to said substrate.

10. (AMENDED) An apparatus as defined in claim 9, wherein the ultraviolet light has a wavelength in a range of 242.4 to 300nm.

11. (AMENDED) An apparatus as defined in claim 9, wherein said cleaning solution includes a base.

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17. (AMENDED) A substrate treating method for removing film from a substrate by supplying a treating solution thereto, comprising the steps of:
supplying said treating solution having ozone dissolved therein to said substrate; and

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subsequently irradiating said treating solution supplied to said substrate with ultraviolet light.

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25. (AMENDED) A substrate treating apparatus for removing film from a substrate by supplying a treating solution thereto, comprising:

a support that supports said substrate;
a treating solution supply that supplies said treating solution having ozone dissolved therein to said substrate;
an ultraviolet emitter that emits ultraviolet light to said substrate; and
a control that controls the ultraviolet emitter so that, during a film removing process in which said treating solution is supplied from said treating solution supply to said substrate supported by said support, said ultraviolet emitter emits ultraviolet light to said treating solution supplied to said substrate.

26. (AMENDED) An apparatus as defined in claim 25, wherein the ultraviolet light has a wavelength in a range of 242.4 to 300nm.